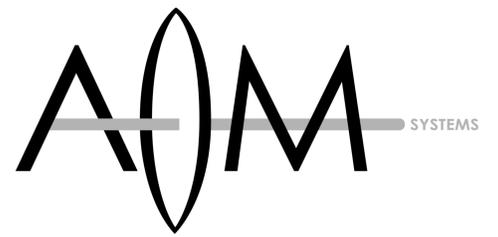
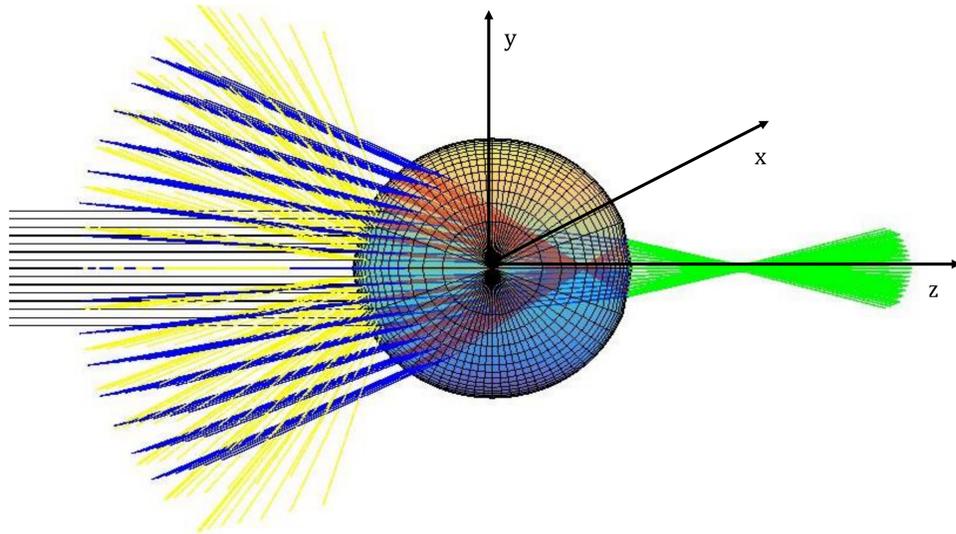


Light Scattering from a Drop with an Embedded Spherical Particle for the Time-Shift Technique



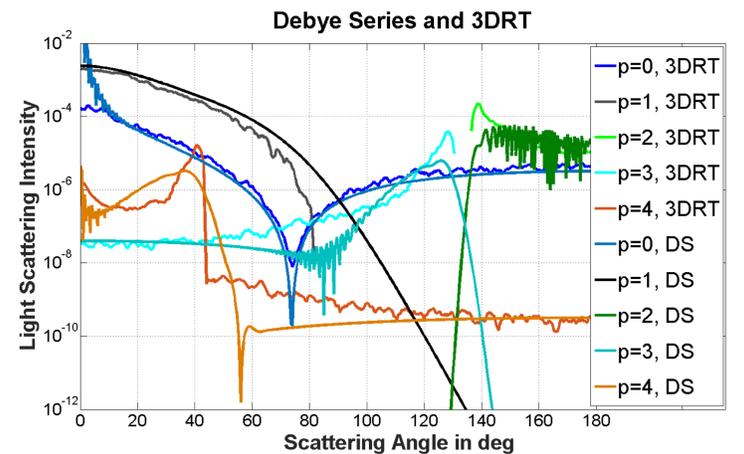
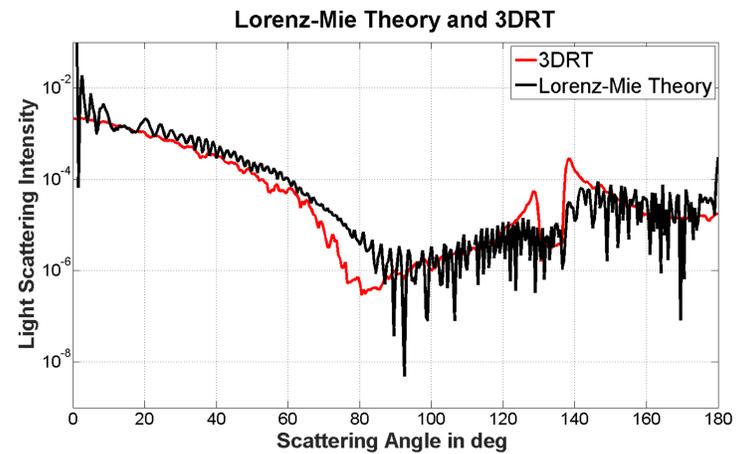
3-Dimensional Ray Tracing Technique (3DRT)



This study is devoted to light scattering from drops with an embedded, reflecting particle, as would be expected in an encapsulation / coating process or with spraying of metallic paints. The present study falls within a broader effort to explore the possibility of utilizing the time-shift technique for such characterization tasks. Ray tracing is used, computing the trajectories of a large number of incident rays defined by an incident plane wave and superimposing all rays scattered in a given direction to result in a scattering diagram. Rays up to $p=10$ are used to compute the scattered light intensity field. The scattering intensity for higher order refraction is computed according to

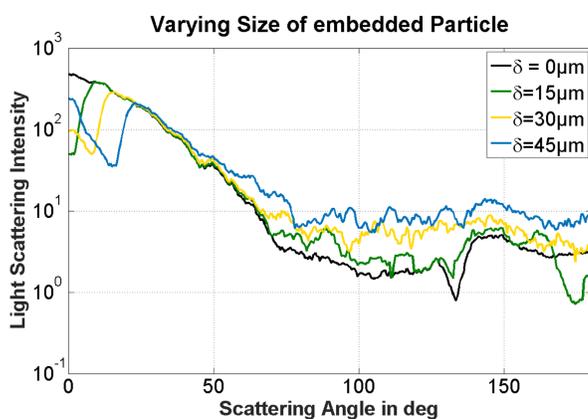
$$I_j(\theta_s, p > 0) = \frac{I_0}{4R^2} d^2 \frac{\sin(\theta_i)\cos(\theta_i)}{\sin(\theta_s)} \frac{\sqrt{m^2 - \sin^2(\theta_i)}}{2[p \cos(\theta_i) - \sqrt{m^2 - \sin^2(\theta_i)}]} \left[\left(1 - r_j^2(m, \theta_s)\right) \left(-r_j(m, \theta_s)\right)^{p-1} \right]^2$$

Verification of the simulations is performed through comparison with selected, known solutions.

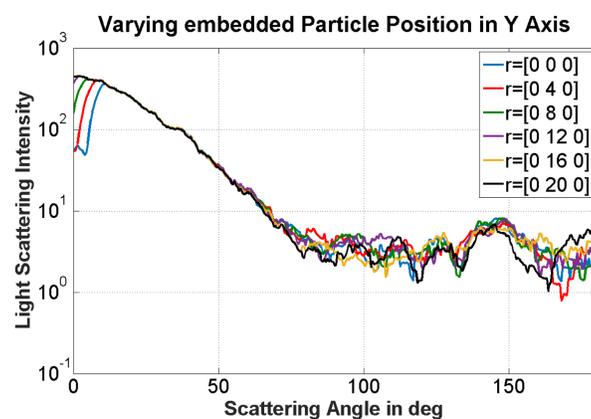


P polarization, $d=100\mu\text{m}$, $n=1,33$, $\lambda=633\text{nm}$

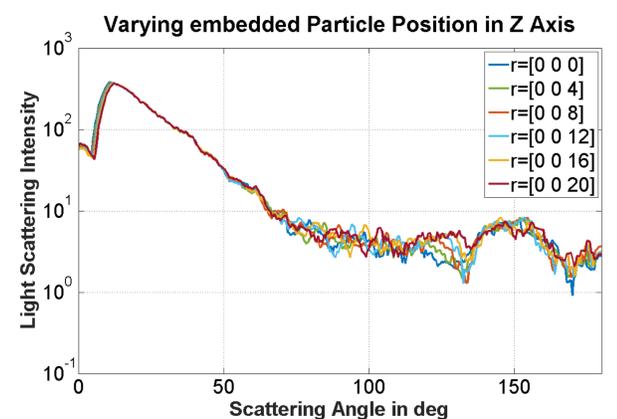
Light Scattering Diagram for a Drop with an embedded Particle



$d=100\mu\text{m}$, $\delta \in \{0, 15, 30, 45\}\mu\text{m}$
 $(r_x, r_y, r_z) = (0, 0, 0)\mu\text{m}$

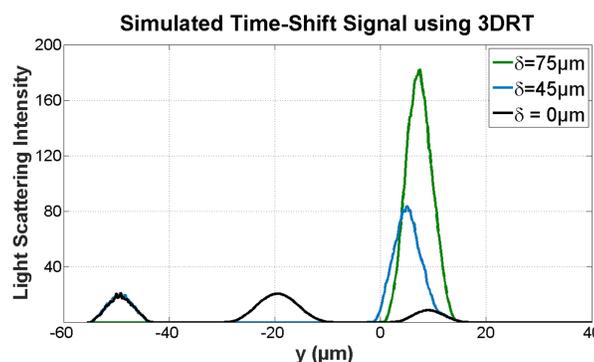
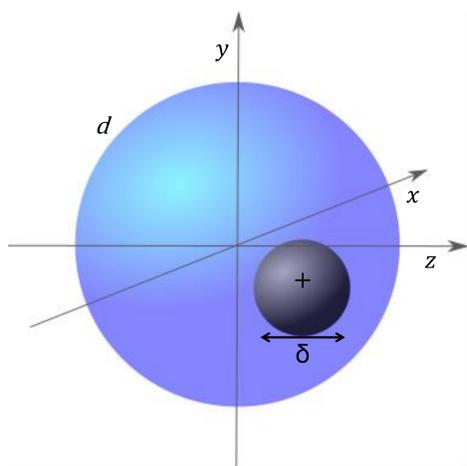


$d=100\mu\text{m}$, $\delta=20\mu\text{m}$
 $r_y \in \{0, 4, 8, 12, 16, 20\}\mu\text{m}$



$d=100\mu\text{m}$, $\delta=20\mu\text{m}$
 $r_z \in \{0, 4, 8, 12, 16, 20\}\mu\text{m}$

Light Scattering Simulation for the Time-Shift Technique



The ray tracing program can simulate a time-shift signal for a drop containing an embedded particle. In this case the incident wave is a highly focused Gauss beam.

The scattering light from a drop including an embedded particle at the detector location is given by

$$I_p(x) \rightarrow S_p(t) = \sum_i A_i f_i(t_0^{(i)}) + \xi_i(\delta, d, r)$$

where the distortion $\xi_i(\delta, d, r)$ depends on drop size (d), particle size (δ) and its location (r).